

Specification Amendment:

Please amend the paragraph on page 6, lines 10-17, as follows:

In the first step of the process, coating with the element having no catalytic ability by itself may be performed by vacuum deposition, electrochemical deposition or sputtering.

Vacuum deposition is preferred since it facilitates consistent generation of thin films. The amount of deposition is preferably between 5 nm and 100 μm , more preferably between 0.05 and 5 μm , in terms of thickness. ~~After coating with the element having no catalytic ability by itself, the second step is then operated without any complicated intermediate step, such as anodization.~~

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